

Libraries

Name	Process	Form Factor
RGO_GF22_18V33_FDX_40C_RF	FDX	Inline CUP

Summary

The RF library provides Analog / RF I/O cells including LNA input pads, a 5V tolerant PA output pad and a 10GHz analog signal pad with multiple input resistance options. Discrete components (RF diodes and SCR's) are provided to enable construction of a custom ESD protection solution.

This 22nm library is available in an inline CUP wire bond implementation with a flip chip option.

To design a functional I/O power domain with these analog / RF cells, the 3.3V Support: Power library is required. That library contains the power cells used as part of the overvoltage / ESD protection solution.

ESD Protection:

- JEDEC compliant
 - 2KV ESD Human Body Model (HBM)
 - 500 V ESD Charge Device Model (CDM)

Latch-up Immunity:

- JEDEC compliant
 - Tested to I-Test criteria of $\pm 100\text{mA}$ @ 125°C

RF Diodes

A set of PPLUS_NWELL_DIODE RF diodes provide minimum capacitance for RF applications and high current handling capability for good ESD protection.

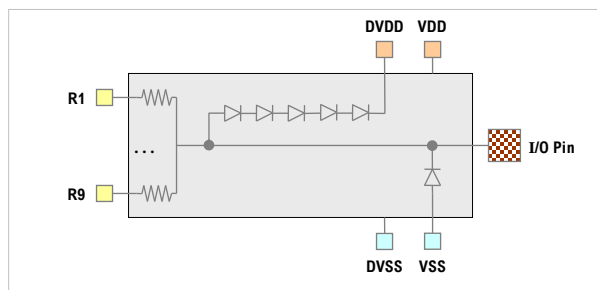
Silicon-Controlled Rectifiers (SCR)

A set of P+ to Nwell SCR discrete components provide the lowest capacitance with the highest ESD protection. These components have been used in I/O pads to demonstrate over 6KV ESD protection.

ANP_BI_DWR_5T

ANP_BI_DWR_5T is a bi-directional analog signal pad with selectable input resistance. Resistors R1 to R4 and R6 to R9 can be used in parallel to achieve the desired resistance value as low as 1.3 ohms.

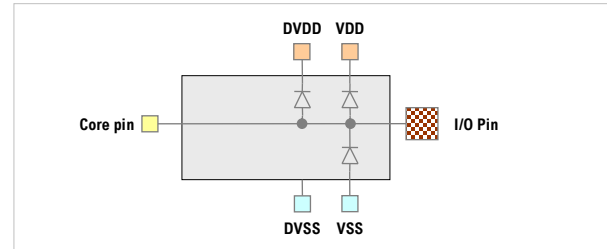
This structure can then be used with output amplifiers for which R5 can be used in the feedback path. If used in this manner, R1 to R4 and R6 to R9 should be individually connected to isolated fingers of the driver transistors.



Analog / RF Pads

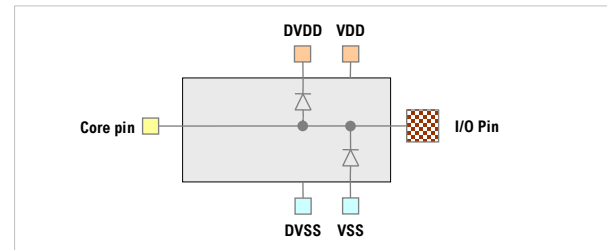
ANP_IN_LNA_1033V

ANP_IN_LNA_10V is a 0 to 0.8V analog I/O pad optimized for low capacitance and designed to protect thin gate oxide input devices. The layout uses wide metal 3 interconnect (14 μm) for low inductance from the bond pad to the core. Additional variants (_UVT & _OVT) provide lower capacitance and the ability to handle occasional signal undershoot / overshoot of 0.7V.



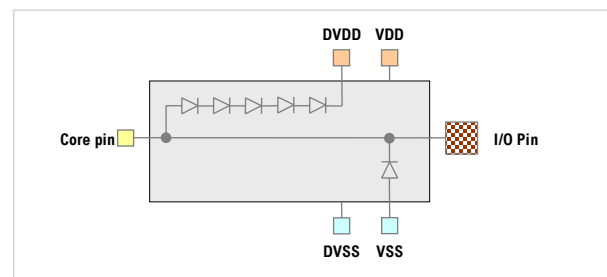
ANP_IN_LNA_33V

ANP_IN_LNA_33V is a 0 to 3.3V analog I/O pad optimized for low capacitance. The layout uses wide metal 3 interconnect (12 μm) for low inductance from the bond pad to the core.



ANP_OU_PWA_5T

ANP_OU_PWA_5T is an analog I/O pad optimized for low capacitance which uses SCRs for ESD clamp devices. The stacked diode ESD structure from DVDD to the I/O pin provides extended overvoltage protection. With a 3.3V power supply, this I/O pad is 5V tolerant. Dropping to an I/O domain power supply of 1.8V, the pad is 3.3V tolerant.



Recommended operating conditions

	Description	Min	Nom	Max	Units
V _{VDD}	Core supply voltage	0.72	0.80	0.88	V
		2.97	3.3	3.63	V
		2.25	2.5	2.75	V
V _{DVDD}	I/O supply voltage	1.62	1.8	1.98	V
		1.08	1.2	1.32	V
T _J	Junction temperature	-40	25	125	°C
V _{PAD}	Voltage at PAD	V _{DVSS} -0.3	-	V _{DVDD} +0.3	V

Characterization Corners

Nominal VDD	Model	VDD	DVDD ^[1]	Temperature
0.8V	FF	+10%	+10%	-40°C
	FF	+10%	+10%	125°C
	TT	nominal	nominal	25°C
	TT	nominal	nominal	85°C
	SS	-10%	-10%	-40°C
	SS	-10%	-10%	125°C

[1] DVDD = 1.2V, 1.8V, 2.5V & 3.3V

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Published by:

Aragio Solutions
2201 K Avenue
Section B Suite 200
Plano, TX 75074-5918
Phone: (972) 516-0999
Fax: (972) 516-0998
Web: <http://www.aragio.com/>

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Printed in the United States of America